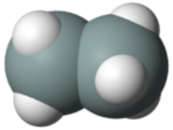
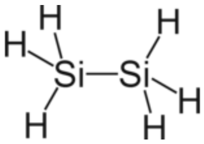
Mitsui Chemicals

Disilane Si_2H_6

Features

- Purity : 99.99%
- Physical state : Gas (liquefied gas)
- Appearance : Compressed liquefied gas in high-pressure gas cylinder
- Boiling point : -14.5 °C
- Melting point : -132.5 °C
- Vapor pressure : 435.6 kPa (at 30 °C)





Applications

- Specialty gas as an agent for Chemical Vapor Deposition(CVD) of silicon film such as poly-Si, SiNx and SiOx in semiconductor industry

Customers

- Mitsui Disilane has been widely used among global leading semiconductor companies among IC chip makers, foundry makers, DRAM and NAND makers for decades